

ABSTRACT

[Problem] To provide an information processing device that enables the appropriate prediction of reliability information of a polishing endpoint detection function, which indicates the reliability of the endpoint detection function for detecting that chemical mechanical polishing has reached its endpoint.

[Solution] An information processing device 5 includes: an information acquisition unit 500 that acquires reliability degradation factor state information in a chemical mechanical polishing process of a substrate performed by a substrate processing device 2, the reliability degradation factor state information including at least one of wear state information indicating a wear state of components of the substrate processing device 2 and processing state information indicating a processing state during polishing; and a state prediction unit 501 that predicts reliability information of a polishing endpoint detection function for the reliability degradation factor state information by inputting the reliability degradation factor state information acquired by the information acquisition unit 500 into a learning model that has been trained through machine learning to learn a correlation between the reliability degradation factor state information and reliability information of the polishing endpoint detection function that indicates reliability of an endpoint detection function that detects that the chemical mechanical polishing process has reached an endpoint.

FIG. 13